

**ATTENUATION TYPE PHASE SHIFT MASK AND ITS PRODUCTION**

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**JAPIO Keywords:**

- R003 (ELECTRON BEAM)

**Abstract:**

PURPOSE: To provide an attenuation type phase shift mask having patterns to prevent generation of light intensity regions (side lobe images) generated around the light transmissive parts of the attenuation type phase shift mask.

CONSTITUTION: The prescribed regions of phase shifter parts 10 near the circumferences of the light transmissive parts 20 are provided with auxiliary patterns 30 for adjusting the exposure of exposing light to a material to be exposed corresponding to these regions. Negation of the light intensity of the side lobe images is made possible by these auxiliary patterns 30.

JAPIO

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